METHOD OF PROCESSING SUBSTRATE, METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE, PROGRAM, SUBSTRATE PROCESSING APPARATUS, AND GAS SUPPLY SYSTEM

ABSTRACT

There is provided a technique that includes forming a film on a substrate by performing a cycle a predetermined number of times, the cycle including: (a) supplying an inhibitor to the substrate; (b) supplying a first precursor from a first reservoir to the substrate; (c) supplying a second precursor from a second reservoir to the substrate; and (d) supplying a reactant to the substrate.

Fig. 4